NOTES:
1. SUBSTRATE:
   SINGLE CRYSTAL SILICON

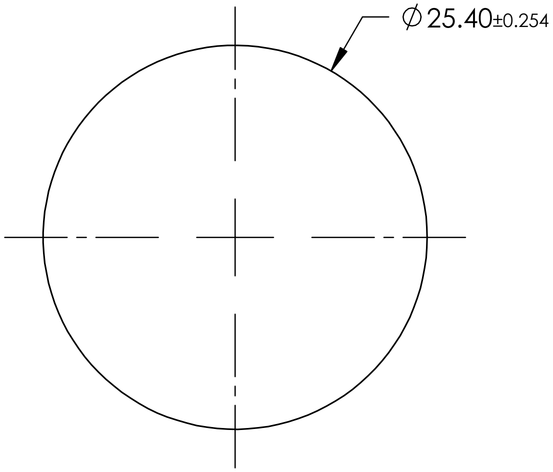
2. COATING (APPLY ACROSS COATING APERTURE):
   Mo/Si MULTILAYER; TOP LAYER Si

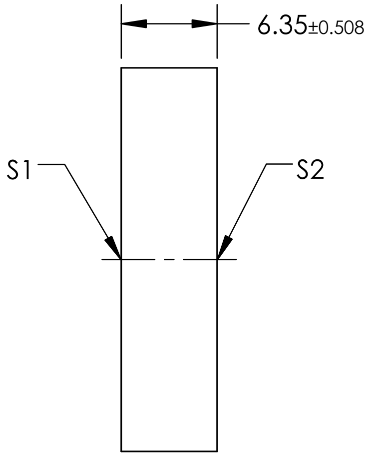
   S1: R(ABS) > 60% @ 13.5nm; FWHM 0.50nm

   S2: NONE

3. WAVELENGTH RANGE (nm): 13.18 - 13.68

FOR INFORMATION ONLY:
DO NOT MANUFACTURE
PARTS TO THIS DRAWING





SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE
DIMENSIONS ARE FOR REFERENCE ONLY

	S1	S2
SHAPE	PLANO	PLANO
SURFACE ROUGHNESS	< 3 Å RMS	N/A
SURFACE FLATNESS	λ/10	N/A
BEVEL	PROTECTIVE AS NEEDED	PROTECTIVE AS NEEDED

Edmund Optics®

THIRD ANGLE PROJECTION		TITLE	13.5nm, 25.4mm DIA, 5° AOI, EUV FLAT MIRROR		
ALL DIMS IN	mm	DWG NO	38759	SHEET 1 OF 1	